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# *Reflection, Scattering, and Diffraction from Surfaces III*

**Leonard M. Hanssen**
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The CID Number appears on each page of the manuscript. The complete citation is used on the first page, and an abbreviated version on subsequent pages. Numbers in the index correspond to the last two digits of the six-digit CID Number.

# Contents

vii *Conference Committee*

**SESSION 1 SCATTERING THEORY I**

8495 02 **Domain of validity of the equation for total integrated scatter (TIS) (Invited Paper)** [8495-1]
J. E. Harvey, N. Choi, CREOL, The College of Optics and Photonics, Univ. of Central Florida (United States)

8495 03 **Upper roughness limitations on the TIS/RMS relationship** [8495-2]
J. C. Stover, The Scatter Works Inc. (United States); S. Schröder, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany); T. A. Germer, National Institute of Standards and Technology (United States)

8495 04 **Comparison of the domain of validity of several approximate surface scatter theories** [8495-3]
N. Choi, J. E. Harvey, CREOL, The College of Optics and Photonics, Univ. of Central Florida (United States)

8495 05 **Converting surface roughness data into PSD and BSDF** [8495-4]
R. N. Pfisterer, Photon Engineering LLC (United States)

**SESSION 2 IMAGING METHODS AND APPLICATIONS I**

8495 06 **Design of combined microscopical and scatterometrical imaging device of surface inspection** [8495-5]
W. Zhao, C. Hahlweg, H. Rothe, Helmut-Schmidt Univ. (Germany)

8495 07 **Backscatter based projectile trajectory measurement under daylight conditions** [8495-6]
U. Chalupka, H. Rothe, Helmut-Schmidt Univ. (Germany)

8495 08 **Surface characterization using combined analysis of original and scatter image** [8495-8]
W. Zhao, C. Hahlweg, H. Rothe, Helmut-Schmidt Univ. (Germany)

**SESSION 3 OPTICAL PROPERTIES: THEORY AND MEASUREMENT**

8495 09 **Inter-laboratory comparison using integrating sphere spectrophotometers to measure reflectance and transmittance of specular, diffuse, and light-redirecting glazing products (Invited Paper)** [8495-9]
J. C. Jonsson, C. Curcija, Lawrence Berkeley National Lab. (United States)

8495 0A **Comparison of NRC goniometric and integrating sphere methods for realizing an absolute diffuse reflectance scale** [8495-10]
R. Baribeau, J. Zwinkels, National Research Council Canada (Canada)

8495 0C **Effective medium analysis on the optical properties of silicon nanowire arrays** [8495-12]
H. Wang, Georgia Institute of Technology (United States) and Harbin Institute of Technology (China); X. Liu, Georgia Institute of Technology (United States); L. Wang, Georgia Institute of Technology (United States) and Arizona State Univ. (United States); Z. Zhang, Georgia Institute of Technology (United States)

## SESSION 4 SCATTERING THEORY II

8495 0F **Estimating hemispherical scatter from incident plane measurements of isotropic samples (Invited Paper)** [8495-15]
J. C. Stover, The Scatter Works Inc. (United States); S. Schröder, A. von Finck, A. Duparré, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany)

8495 0G **A BRDF model for scratches and digs** [8495-16]
G. L. Peterson, Breault Research Organization, Inc. (United States)

8495 0H **Surface-plasmon mediated near-field light diffraction** [8495-17]
D. Huang, L. D. Wellems, Air Force Research Lab. (United States)

8495 0I **How accurate is the Kubelka-Munk theory of diffuse reflection? A quantitative answer** [8495-18]
R. I. Joseph, M. E. Thomas, Johns Hopkins Univ. Applied Physics Lab. (United States)

## SESSION 5 MEASUREMENT INSTRUMENTATION AND APPLICATIONS I

8495 0K **Tunable supercontinuum fiber laser source for BRDF measurements in the STARR II gonioreflectometer** [8495-20]
H. J. Patrick, National Institute of Standards and Technology (United States); C. J. Zarobila, National Institute of Standards and Technology (United States) and Jung Research and Development Corp. (United States); T. A. Germer, V. A. Ying, C. A. Cooksey, B. K. Tsai, National Institute of Standards and Technology (United States)

8495 0M **Scatterometer basing on a STAR GEM idea for optical measurements of microlenses** [8495-22]
E. Kawate, National Institute of Advanced Industrial Science and Technology (Japan) and TRAS, Inc (Japan); M. Hain, National Institute of Advanced Industrial Science and Technology (Japan) and Institute of Measurement Science (Slovakia)

8495 0N **The Southwest Research Institute ultraviolet reflectance chamber (SwURC): a far ultraviolet reflectometer** [8495-23]
G. S. Winters, K. D. Retherford, M. W. Davis, S. M. Escobedo, E. C. Bassett, E. L. Patrick, M. E. Nagengast, M. H. Fairbanks, P. F. Miles, J. W. Parker, G. R. Gladstone, D. C. Slater, S. A. Stern, Southwest Research Institute (United States)

## SESSION 6 IMAGING METHODS AND APPLICATIONS II

8495 0O **The focusing of light scattered from diffuse reflectors using phase modulation (Invited Paper)** [8495-24]
J. M. Schafer, M. A. Marciniak, Air Force Institute of Technology (United States)

8495 0P **Scattering computation for 3D laser imagery and reconstruction algorithms (Invited Paper)** [8495-26]
I. Berechet, SISPIA (France); G. Berginc, Thales Optronique S.A.S. (France); S. Berechet, SISPIA (France)

8495 0Q **Matrix determination of hidden object reflectance by indirect photography** [8495-27]
S. S. Ferrel, M. A. Marciniak, Air Force Institute of Technology (United States)

## SESSION 7 MEASUREMENT INSTRUMENTATION AND APPLICATIONS II

8495 0R **Measuring grazing-angle DHR with the infrared grazing angle reflectometer** [8495-28]
M. R. Benson, M. A. Marciniak, Air Force Institute of Technology (United States); J. W. Burks, Air Force Research Lab. (United States)

8495 0T **Advanced gloss sensing for robotic applications** [8495-30]
C. Deinhammer, M. Brandner, Technische Univ. Graz (Austria)

## SESSION 8 MEASUREMENT AND ANALYSIS TECHNIQUES

8495 0V **Sophisticated light scattering techniques from the VUV to the IR regions (Invited Paper)** [8495-31]
S. Schröder, M. Trost, T. Herffurth, A. von Finck, A. Duparré, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany)

8495 0W **Effects of a measurement floor on Mueller matrix measurements in a DRR BSDF system** [8495-32]
S. E. Nauyoks, M. A. Marciniak, Air Force Institute of Technology (United States)

8495 0X **Using differential ray tracing in stray light analysis** [8495-33]
D. F. Rock, The Aerospace Corp. (United States)

8495 0Y **Optical non-contact micrometer thickness measurement system for silica thick films** [8495-34]
K. Thambiratnam, H. Ahmad, Univ. of Malaya (Malaysia); M. Yasin, Univ. Airlangga (Indonesia); A. Z. Zulkifli, S. W. Harun, Univ. of Malaya (Malaysia)

## SESSION 9 MEASUREMENT INSTRUMENTATION AND APPLICATIONS III

8495 0Z **Extensive goniometric spectral measurements at desert sites for military engineering (Invited Paper)** [8495-35]
T. E. Berry Jr., J. C. Morgan, J. S. Furey, T. A. DeMoss, J. R. Kelley, J. R. McKenna, U.S. Army Engineer Research and Development Ctr. (United States)

8495 10 **Optimized diffusers for reflective mirasol displays: experience from metrology characterization** [8495-36]
E. Y. Poliakov, R. A. Martin, I. Bita, M. Sampsell, Qualcomm MEMS Technologies, Inc. (United States)

## POSTER SESSION

8495 12 **Roughness evaluation of very smooth surfaces using a novel method of scatter measurement** [8495-38]
R. Synak, W. Lipinski, M. Pawelczak, Institute of Mathematical Machines (Poland)

8495 14 **Reflectance variability of surface coatings reveals characteristic eigenvalue spectra** [8495-40]
J. M. Medina, Univ. do Minho (Portugal); J. Díaz, Univ. de Granada (Spain); R. Barros, Univ. do Minho (Portugal)

8495 17 **Homogeneity measurements of hardness standards with a nondestructive optical method** [8495-44]
J. G. Suarez-Romero, E. Hernandez-Gomez, Instituto Tecnológico de Querétaro (Mexico); J. B. Hurtado-Ramos, Ctr. de Investigación en Ciencia Aplicada y Tecnología Avanzada (Mexico)

8495 18 **A fast and accurate surface plasmon resonance system** [8495-45]
Y. M. Espinosa Sánchez, D. Luna Moreno, E. Noé Arias, G. Garnica Campos, Ctr. de Investigaciones en Óptica, A.C. (Mexico)

8495 19 **Electromagnetic scattering in the open elliptic quantum billiard** [8495-46]
H. Garcia-Gracia, J. C. Gutiérrez-Vega, Tecnológico de Monterrey (Mexico)

*Author Index*

# Conference Committee

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**Benjamin K. Tsai**, National Institute of Standards and Technology (United States)

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1 Scattering Theory I
**John C. Fleming**, Ball Aerospace & Technologies Corporation (United States)

2 Imaging Methods and Applications I
**Richard N. Pfisterer**, Photon Engineering LLC (United States)

3 Optical Properties: Theory and Measurement
**Brian G. Hoover**, Advanced Optical Technologies (United States)

4 Scattering Theory II
**Alexei A. Maradudin**, University of California, Irvine (United States)

5 Measurement Instrumentation and Applications I
**Hsueh-Mei W. Graham**, Lockheed Martin Aeronautics Company (United States)

6 Imaging Methods and Applications II
**Hendrik Rothe**, Helmut-Schmidt University (Germany)

7 Measurement Instrumentation and Applications II
**Danhong Huang**, Air Force Research Laboratory (United States)

8 Measurement and Analysis Techniques
**Andrea M. Brown**, Johns Hopkins University Applied Physics Laboratory (United States)

9 Measurement Instrumentation and Applications III
**Benjamin K. Tsai**, National Institute of Standards and Technology (United States)

Panel Discussion: Methods and Applications of Deflectometry
**Peng Su**, *Moderator*, College of Optical Sciences, The University of Arizona (United States)
**Jan Burke**, *Moderator*, Bremer Institut für angewandte Strahltechnik
**Christian Faber**, *Panelist*, Universität Erlangen-Nürnberg (Germany)
**Robert E. Parks**, *Panelist*, College of Optical Sciences, The University of Arizona (United States)